PATENT

y Docket No.: 5308-412

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

În re: Saxler Application No.: 10/849,589

Group Art Unit: 2811 Examiner: Wael M. Fahmy

Confirmation No.: 6346

Filed: May 20, 2004

For:

SEMICONDUCTOR DEVICES HAVING A HYBRID CHANNEL LAYER, CURRENT

APERTURE TRANSISTORS AND METHODS OF FABRICATING SAME

Date: August 24, 2004

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Sir:

Attached is a list of documents on Form PTO-1449, together with a copy of any listed foreign patent document and/or non-patent literature. A copy of any listed U.S. patent and/or U.S. patent application publication is not provided herewith in accordance with the waiver by the U.S. Patent and Trademark Office of requirements under 37 C.F.R. § 1.98(a)(2)(i) for all U.S. national patent applications filed after June 30, 2003 and for all international applications that have entered the national stage under 35 USC § 371 after June 30, 2003.

It is requested that these documents be considered by the Examiner and officially made of record in accordance with the provisions of 37 C.F.R. § 1.56 and Section 609 of the MPEP.

This Information Disclosure Statement is submitted in accordance with 37 C.F.R. § 1.97(b), within three months of the filing date of the above-referenced application or before the mailing of a first Office Action on the merits, whichever event occurs last. Therefore, no fee is believed due. However, the Commissioner is hereby authorized to charge any deficiency or credit any overpayment to Deposit Account No. 50-0220.

Respectfully submitted,

Elizabeth A. Stanek Registration No. 48,568

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Application Number	10/849,589
Filing Date	May 20, 2004
First Named Inventor	Saxler
Group Art Unit	2811
Examiner Name	Wael M. Fahmy
Attorney Docket Number	5308-412

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INFORM	IATION DIS	CLOSUR	E	Filing Date	May 20, 2004	
STATE	STATEMENT BY APPLICANT (use as many sheets as necessary)			First Named Inventor	Saxler	-
				Group Art Unit	2811	
(use as m				Examiner Name	Wael M. Fahmy	
Sheet	A2	of	A4	Attorney Docket Number	5308-412	

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(use as n				Examiner Name	Wael M. Fahmy	
Sheet	A3	of	A4	Attorney Docket Number	5308-412	

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	Signature	Date Considered	_

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Examiner Signature	Date Considered	